

CLAIMS

1. A lithocell comprising:
 - a lithographic apparatus, comprising:
 - an illuminator configured to provide a beam of radiation,
 - a support structure configured to hold a patterning device, the patterning device configured to impart the beam with a pattern in its cross-section,
 - a substrate table configured to hold a substrate, and
 - a projection system configured to project the patterned beam onto a target portion of the substrate;
 - a track comprising one or more processing devices; and
 - a transport system configured to transport the substrate along an elongate transporter pathway between the track and the lithographic apparatus.
2. A lithocell according to claim 1, wherein the transport system comprises its own mini-environment.
3. A lithocell according to claim 1, wherein the track and the lithographic apparatus are placed side by side and the transport system comprises a linear transporter pathway between them.
4. A lithocell according to claim 1, wherein the transport system comprises at least two transporter pathways, one configured to transport the substrate from the track to the lithographic apparatus and one configured to transport the substrate from the lithographic apparatus to the track.
5. A lithocell according to claim 1, wherein the transport system comprises at least one transport robot configured to transport the substrate along the transporter pathway.
6. A lithocell according to claim 1, wherein the transport system serves a plurality of lithographic apparatuses.

7. A lithocell according to claim 1, wherein the transport system comprises a plurality of tracks.
8. A lithocell according to claim 1, wherein the transport system serves at least one of a substrate process apparatus and a substrate metrology apparatus to form an extended substrate assembly line.
9. A lithocell according to claim 1, wherein the transport system is formable to a desired shape.
10. A lithocell according to claim 1, wherein the transport system comprises one or more transporter pathways configured to transport a substrate between different processing devices of the track.
11. A lithocell according to claim 1, wherein the transport system comprises a conveyor in the form of a shuttle on a linear guide actuated by one of an electric motor and a pneumatic motor.
12. A lithocell according to claim 11, wherein the linear guide is one of a roller bearing guide and a gas bearing guide.
13. A lithocell according to claim 1, wherein the transport system comprises a conveyor belt with at least one of a pin and a wire loop configured to support the substrate transported thereon.
14. A lithocell according to claim 1, comprising a gangway set apart from the transport system configured to allow passage a distance away from the transport system.
15. A lithocell comprising:
 - a lithographic apparatus, comprising:
 - an illuminator configured to provide a beam of radiation,
 - a support structure configured to hold a patterning device, the patterning device

configured to impart the beam with a pattern in its cross-section,
a substrate table configured to hold a substrate, and
a projection system configured to project the patterned beam onto a target portion of
the substrate;
a track comprising one or more processing devices; and
a transport system, external to the track and lithographic apparatus, configured to
transport the substrate between the track and the lithographic apparatus, the transport system
comprising a robot arm pivotable about an axis at its first end and adapted to hold a substrate
at its opposite end.

16. A lithocell according to claim 15, wherein the transport system comprises its own mini-environment.

17. A lithocell according to claim 15, wherein the transport system serves a plurality of
lithographic apparatuses.

18. A lithocell according to claim 15, wherein the transport system comprises a plurality of
tracks.

19. A lithocell according to claim 15, wherein at least two lithographic apparatus and at
least two tracks are disposed around the robot arm.

20. A lithocell according to claim 15, wherein the transport system serves at least one of a
substrate process apparatus and a substrate metrology apparatus to form an extended substrate
assembly line.

21. A device manufacturing method using a lithocell comprising a lithographic apparatus
and a track comprising:

- applying a radiation-sensitive material to a substrate in the track;
- transporting the substrate to the lithographic apparatus from the track using a transporter
between them; and
- projecting a patterned beam of radiation onto a target portion of the substrate.

22. A device manufacturing method according to claim 21, wherein the transporter is configured to transport the substrate along an elongate transporter pathway between the track and the lithographic apparatus.
23. A device manufacturing method according to claim 21, wherein the transporter, external to the track and lithographic apparatus, is configured to transport the substrate between the track and the lithographic apparatus by a robot arm pivotable about an axis at its first end and adapted to hold a substrate at its opposite end.